

Fig. ESI1: Temperature dependence of the electrical resistance of the micro-heater employed to determine the TCR. A linear relationship between resistance and temperature is measured.

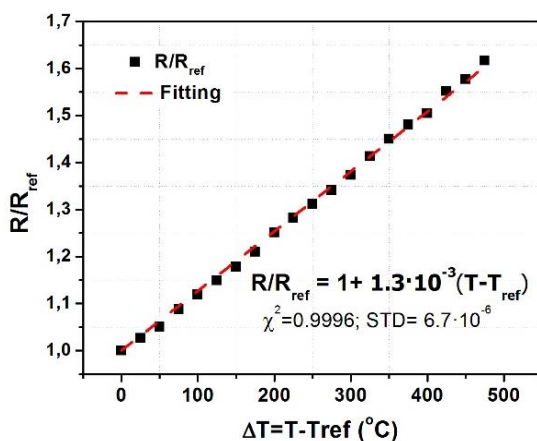


Fig. ESI2: Distribution of temperature in steady-state when a power of 6.5 W is applied to the thin film heater and the micro-reformer is under vacuum (i.e. without fuel flowing). The holey structure reaches a homogeneous temperature of 915 °C, whereas a temperature of 504 °C is obtained in the bulk frame.

